

Tantalum Nitride (TaN) Sputtering Targets

Material Type	Tantalum Nitride	Theoretical Density (g/cc)	16.3
Symbol	TaN	Z Ratio	**1.00
Color/Appearance	Black, Crystalline Solid	Sputter	RF, RF-R
Melting Point (°C)	3,360	Max Power Density	20
Purity:	99.99%, 99.95%	(Watts/Square Inch)	
		Type of Bond	Indium